

REMARKS

Claims 39-91 remain in this application. Claims 1-38 have been canceled.

Entry of the above amendments is earnestly solicited. An early and favorable first action on the merits is earnestly requested.

Should there be any matters that need to be resolved in the present application, the Examiner is respectfully requested to contact the undersigned at the telephone number listed below.

The Commissioner is hereby authorized in this, concurrent, and future replies, to charge payment or credit any overpayment to Deposit Account No. 25-0120 for any additional fees required under 37 C.F.R. § 1.16 or under 37 C.F.R. § 1.17.

Respectfully submitted,

YOUNG & THOMPSON

Benoit Castel

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Benoit Castel, Reg. No. 35,041  
745 South 23<sup>rd</sup> Street  
Arlington, VA 22202  
Telephone (703) 521-2297  
Telefax (703) 685-0573  
(703) 979-4709

BC/yr

10/510112

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APPENDIX:

The Appendix includes the following item(s) :

- a new or amended Abstract of the Disclosure
- a Replacement Sheet for Figure of the drawings
- a Substitute Specification and a marked-up copy of the originally-filed specification
- a terminal disclaimer
- a 37 CFR 1.132 Declaration
- a Substitute Specification and a marked-up copy of the originally-filed specification
- a verified English translation of foreign priority document

ABSTRACT OF THE DISCLOSURE

A photosensitive adhesive composition of the polymerisable resin type, the hardening of which occurs by polymerisation and/or reticulation, includes: - initiators for at least one chain polymerisation reaction to guarantee the hardening of the composition and a sufficient quantity of at least one bifunctional monomer, including a photolabile centre with at least one photolabile entity and at least two polymerisable units, connected by covalent skeletons to the photolabile centre and located away from the cleavage sites of the photolabile centre, such that the composition loses the integrity and adhesivity thereof under the influence of a reticulating radiation causing the cleavage of the photolabile sites. The composition is particularly of application in dentistry.